

A Technical Introduction to The Orion He-Ion Microscope

ALIS Corporation
A Carl Zeiss SMT Company

Dr. Bill Thompson
Chief Scientist, International Business Development

December, 2006



- **Brief Introduction to the Orion System**
 - The history
 - The system
- **The Ion Source**
 - A Three Atom Cluster
- **The Column Optics**
 - Designed for Sub-nm Resolution
- **Atomic Level Imaging System**
 - Imaging Modes
 - SE Detection
 - BSI Detection
 - Photon Detection



Orion Applications

- High Resolution Imaging
- Failure Analysis
- Defect Review
- CD Measurement
- Mask Inspection/Characterization & metrology
- Materials Characterization
 - Carbon Nanotubes
 - Magnetic Materials



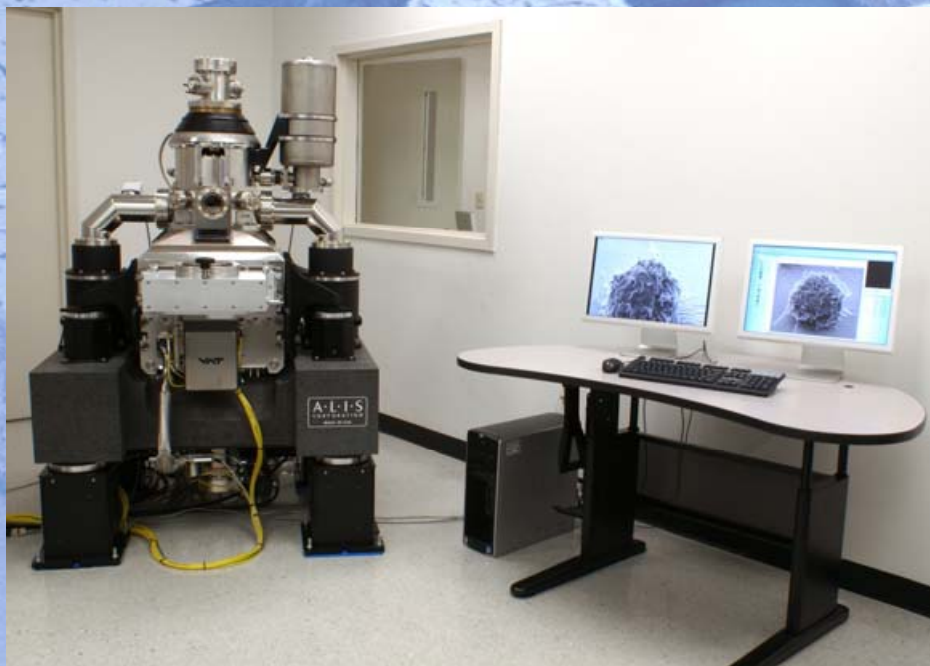
- He-Ion source development started in 1992 (Micrion),
- To date, 40 man-years of research.
- \$30M funding (DARPA, Sematech, Venture Capital & others).

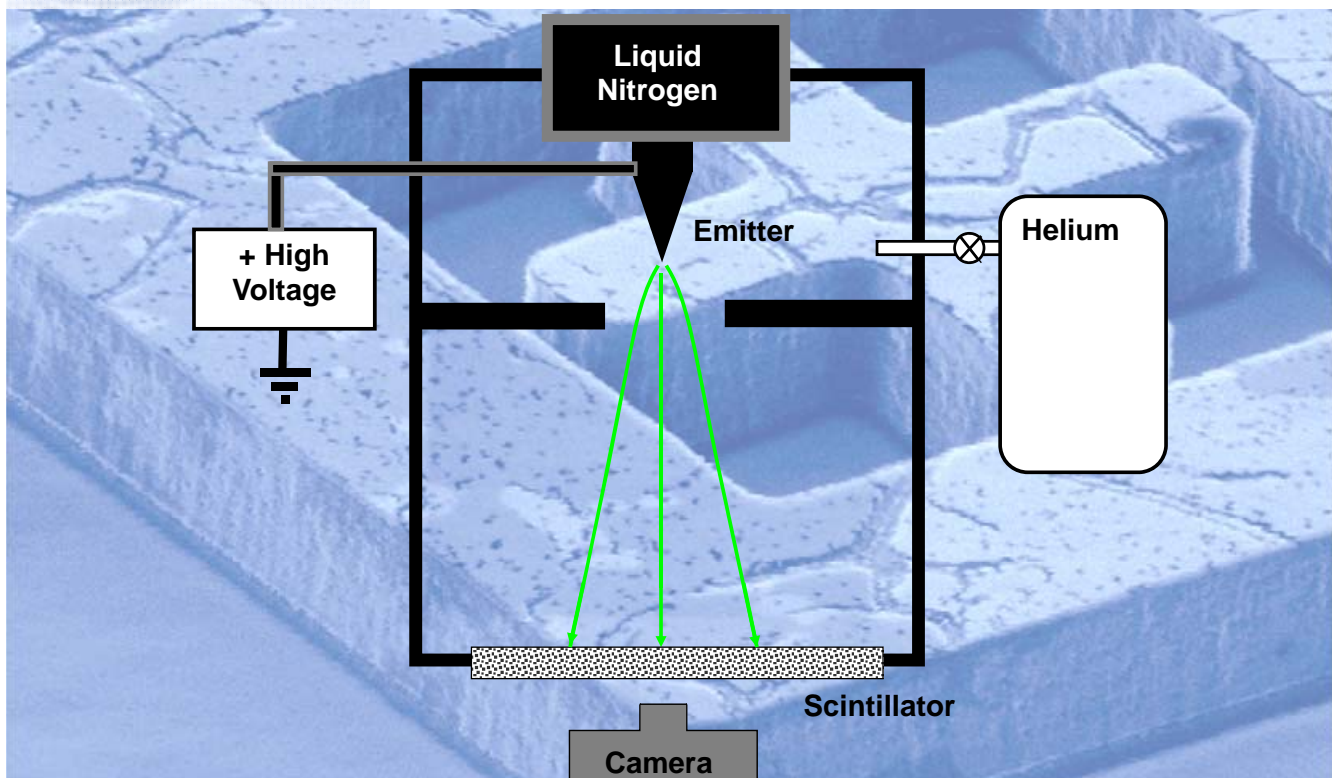


- Development work on ALIS technology began at Micrion, continued at FEI.
- Bill Ward left FEI in 2002, with a license for the technology, to begin the commercialization of the ALIS technology as the ultimate, high resolution microscope.
- ALIS Corporation was funded in March, 2005.
 - Grew to 36 employees by June 2006.
- Carl Zeiss SMT acquired all the stock of ALIS Corporation in July 2006.



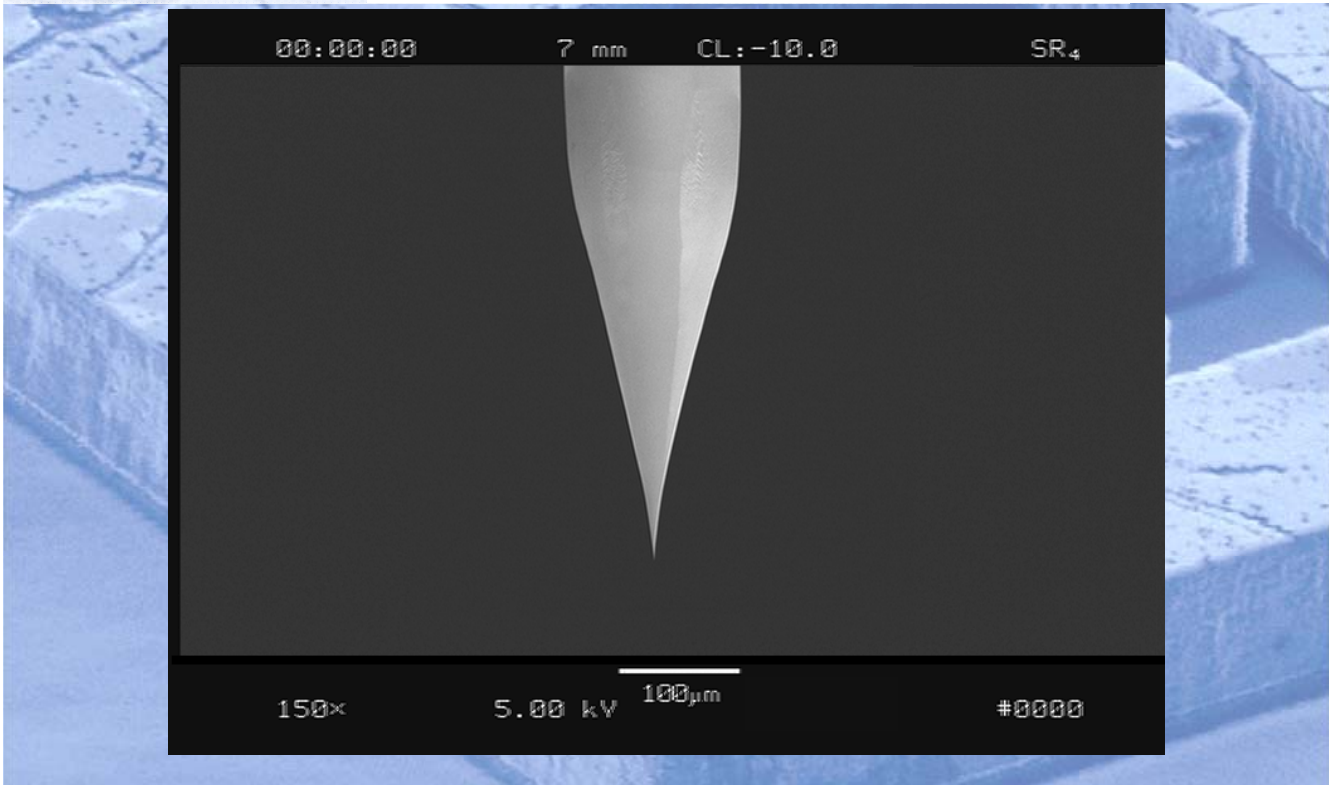
The Orion He-Ion Microscope October 2006





A·L·I·S

ALIS Helium Ion Source From High Altitude



Confidential ALIS/Zeiss Material

Enabling the Nano-Age World®

Slide Number 9



A·L·I·S

Unsharpened ALIS Helium Ion Source – The Field Ion Microscope (FIM) Image

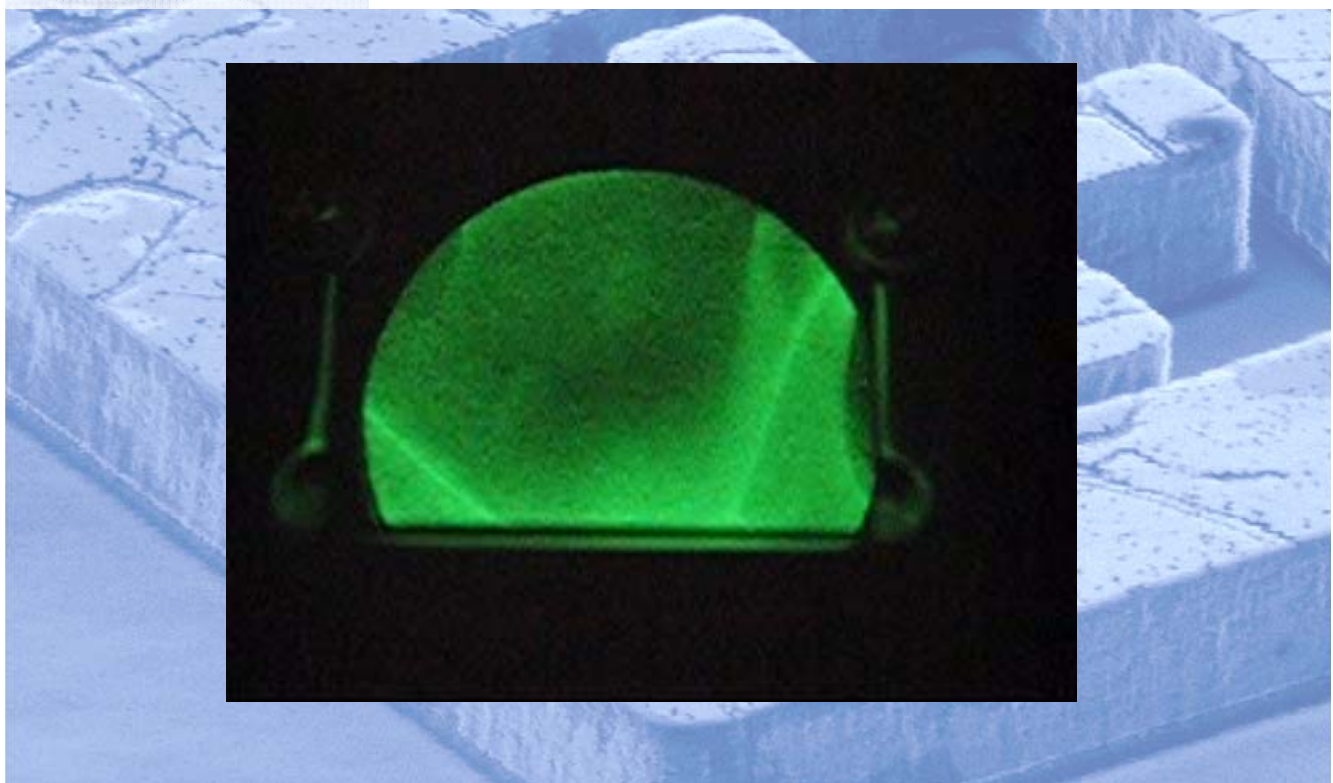
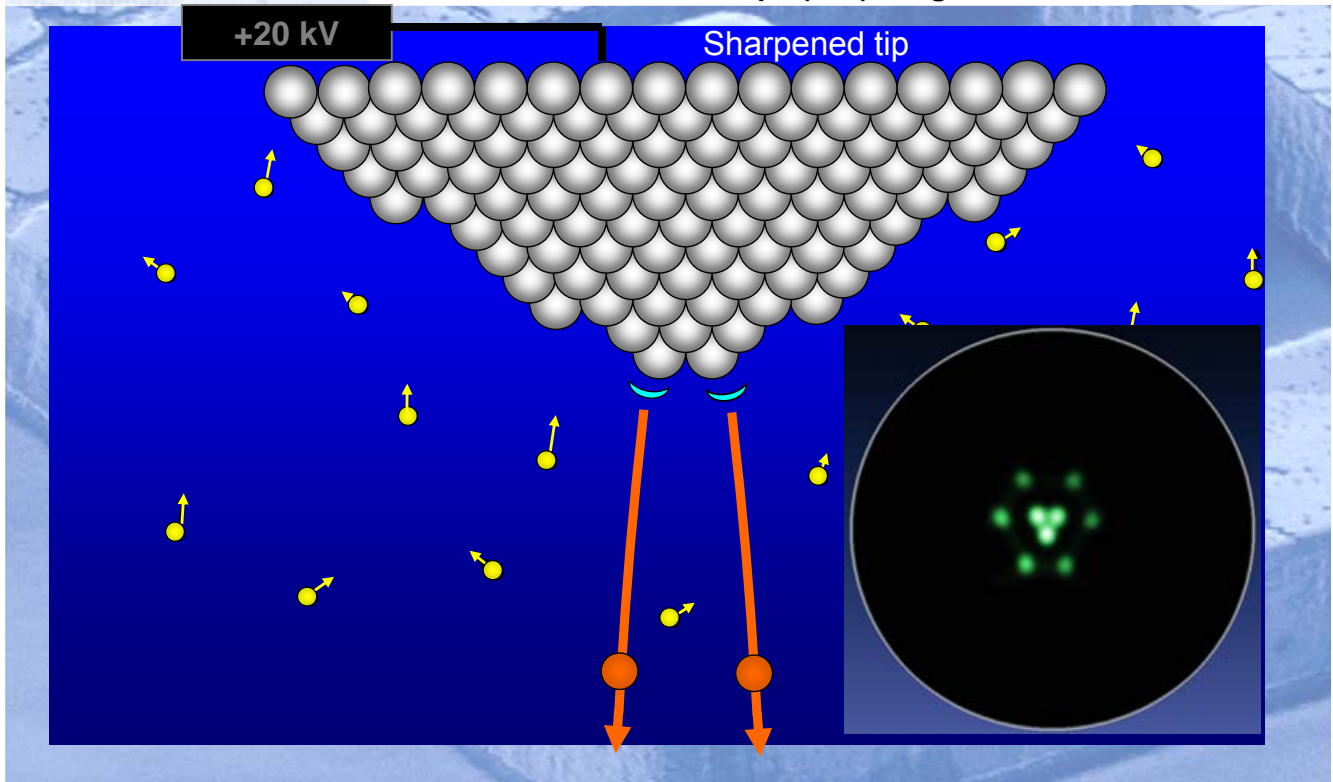


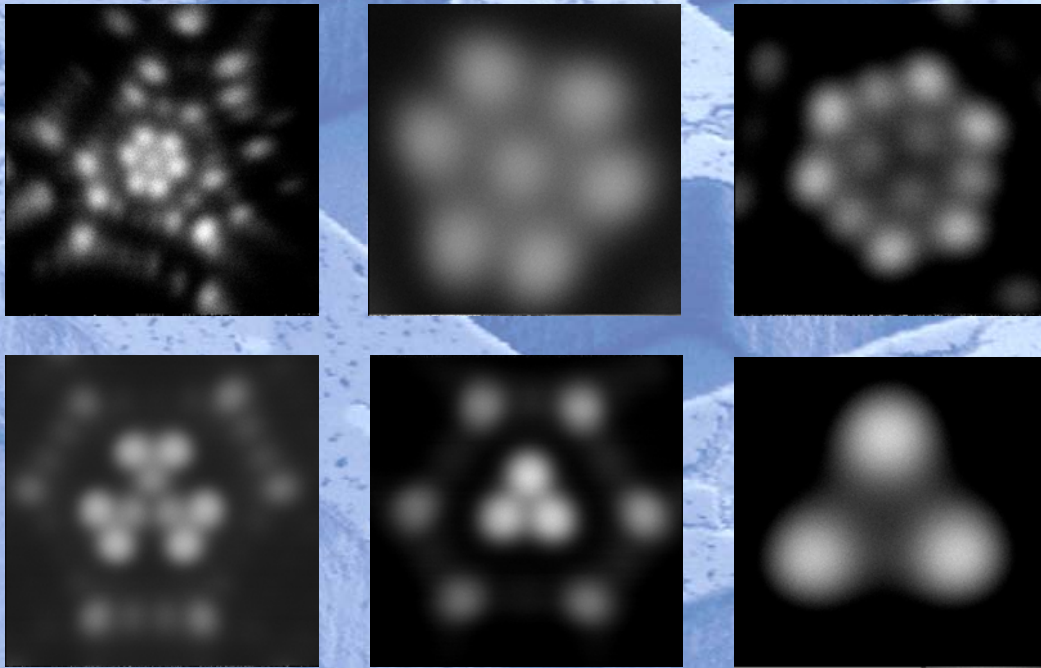
Confidential ALIS/Zeiss Material

Enabling the Nano-Age World®

Slide Number 10





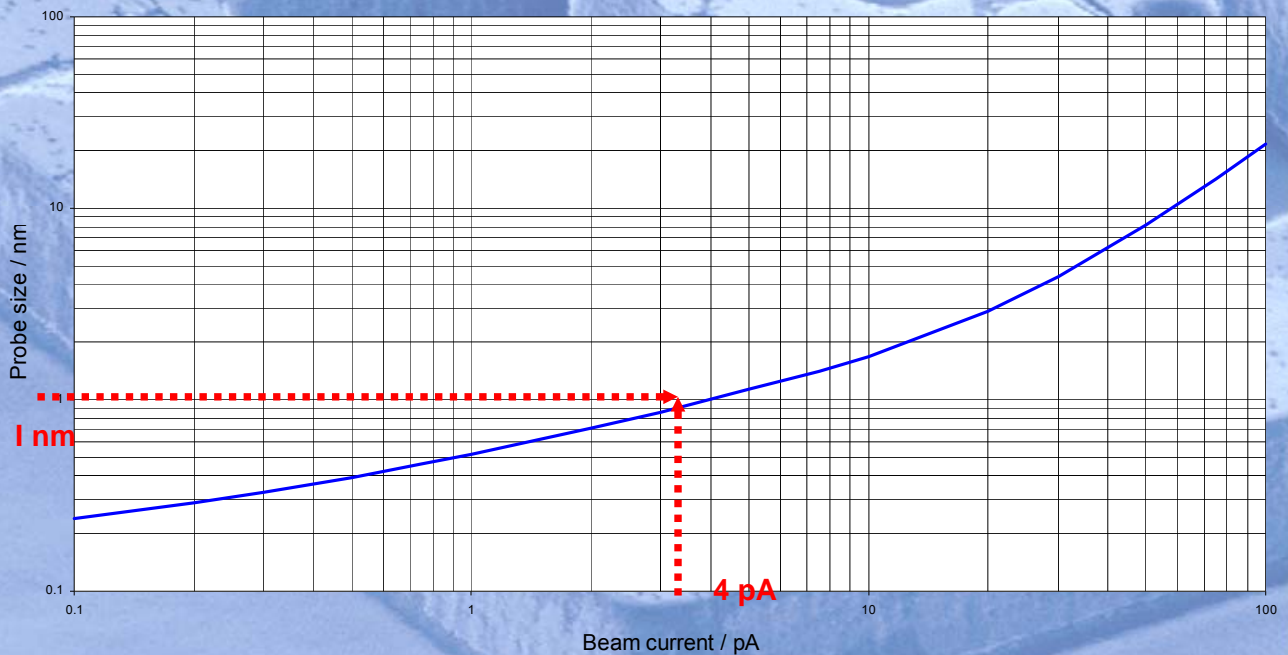


- **High Brightness: $> 10^9$ A/(cm² sr)**
- **Small Virtual Source Size (Sub-Angstrom?)**
- **Low Energy Spread (~0.5 eV)**
- **Diffraction Effects - Reduced Compared to an SEM**
- **Inert Gas - Electrically Inactive in Sample**
- **Long Source Life and Source Stability**



**Calculated Orion Beam
Diameter vs. Beam Current**

Calculated performance plot for ALIS Orion
(Assumes: 40 kV, 4 mm working distance, 1 uA/sr, 0.25 nm)



Confidential ALIS/Zeiss Material

Enabling the Nano-Age World®

Slide Number 15

**ALIS SE Images: Long Depth of Field
Aluminum Crystals ~500um in depth**

ALIS images have a long depth of focus.
About 5X better than SEM under the same conditions.

Confidential ALIS/Zeiss Material

Enabling the Nano-Age World®

Slide Number 16

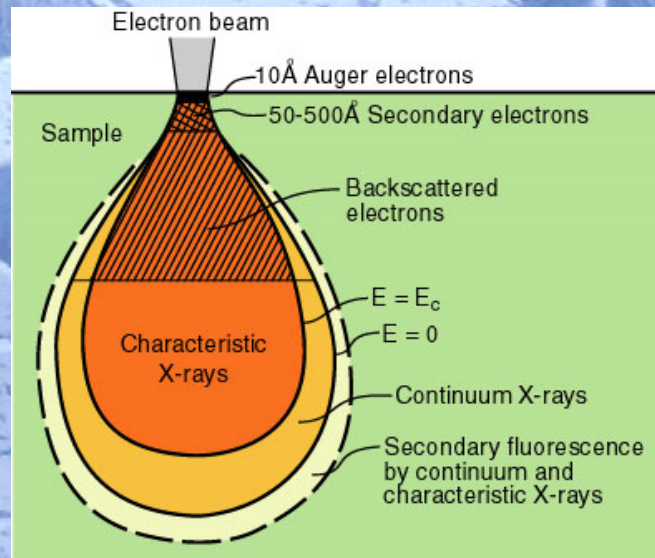


Sample Interaction Volume- What limits the resolution of SEMs?

Secondary electrons:

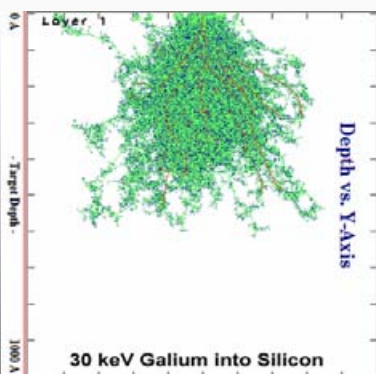
Generated in a 50 to 500 Å region beneath the surface.

The spot size of the probe is not the limiting factor in resolution.



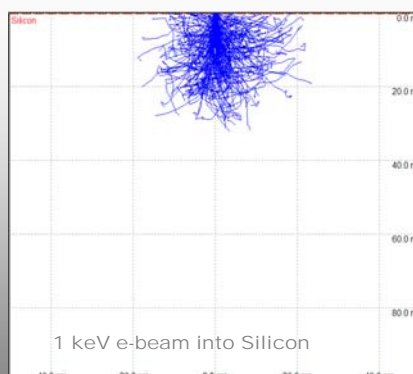
Interaction Volume- The physics behind the resolution. (TRIM & Casino Modelling)

Gallium FIB



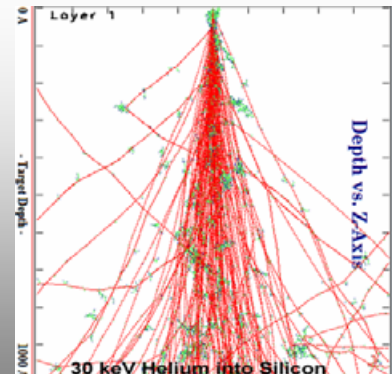
30 keV Gallium into Silicon: Image suffers from large interaction volume at the surface. Many SE's generated from recoils (green and blue).

Standard SEM



1 keV e-beam into Silicon: Image suffers from large interaction volume at the surface. Many SE's are really SE2.

Helium Ion Microscope



30 keV Helium into Silicon: Beam is well collimated beyond the SE escape depth. Recoil contribution is negligible.



– Resolution < 1nm possible because:

- High Source Brightness: $> 10^9$ A/(cm² sr)
- Small Virtual Source Size (Sub-Angstrom)
- Low Energy Spread (~ 0.5 eV)
- No real contribution from diffraction aberrations ~
 - He ion wavelength 1/100th the e⁻ wavelength for comparable energies
- Extremely localized SE launch location due to **low interaction volume**
 - SE's have very low energy and short range in the sample
- Large Depth of Field



▪ **Secondary Electrons Imaging Mode (2 - 8 e⁻ per He⁺);**

- SE Video (gray) Level Contains Some Material Information
- SE Voltage contrast mechanisms can contribute to image information
- Prominent surface & topographical contrast

▪ **Back Scattered Helium Ions (1 per 100 He⁺, as He & He⁺);**

- RBI Rutherford backscatter (RBS) mode
- Contains considerable material information

▪ **Sputtered Target Atoms;**

- (~ 0.02 per He⁺ for Silicon), 1/100th sputtered rate of 30 keV Ga
- Long image times w/ little or no loss of material
- No electrically active implantation
- No fogged or washed out sample image
- No change in electrical properties of the sample

▪ **Photons**

- (~ 1 per 100 He⁺);
- Interesting Application as some organic and dielectric materials are translucent to photons

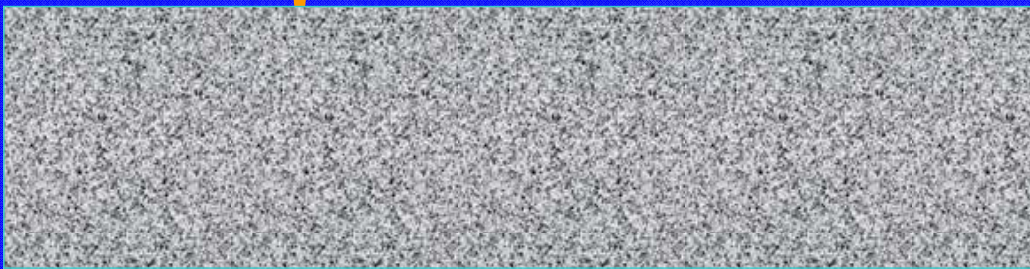
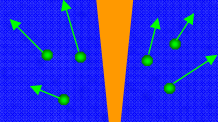
▪ **X-Rays (?)**

- Uncharted region for exploration



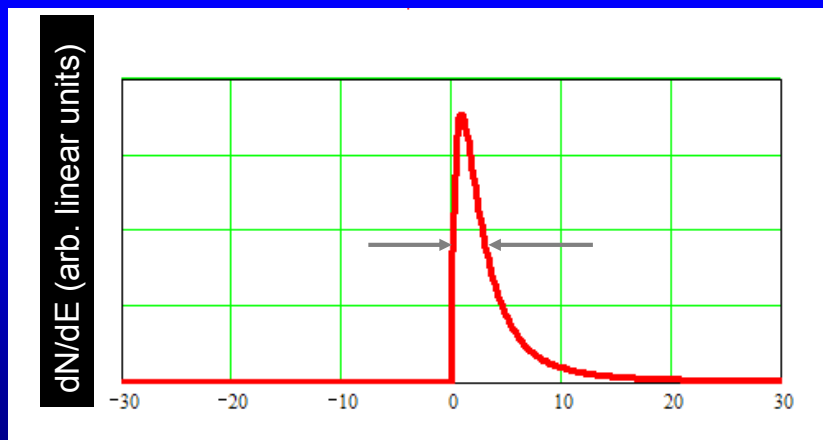
Secondary Electrons:

- Provides true surface information
- Yield varies greatly with material
...ranges from ~2 to ~8
- Yield varies with topography
...varies as $\sec(\alpha)$
- Energy ~ 5 eV

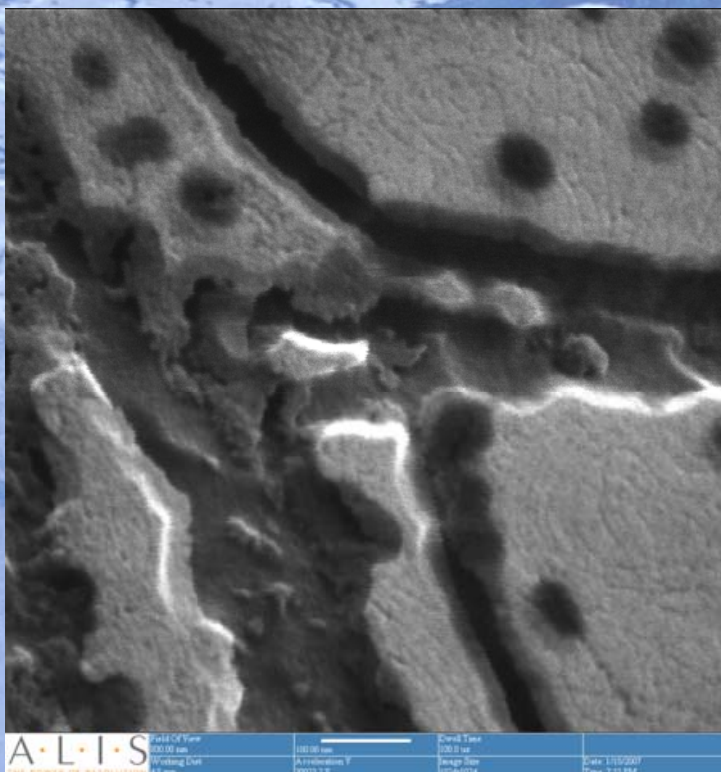


Material	Z	M(amu)	Y_{SE} ($E_{He} = 20 \text{ keV}$, $\alpha_{He} = 0$)
Aluminum	13	27.0	5.31
Silicon	14	28.1	3.38
Titanium	22	47.9	4.65
Iron	26	55.8	4.55
Nickel	28	58.7	5.14
Copper	29	63.4	4.23
Indium	49	114.8	5.69
Tungsten	74	183.8	3.69
Rhenium	75	186.2	3.61
Platinum	78	195.1	8.85
Gold	79	197.0	5.17
Lead	82	207.2	5.57



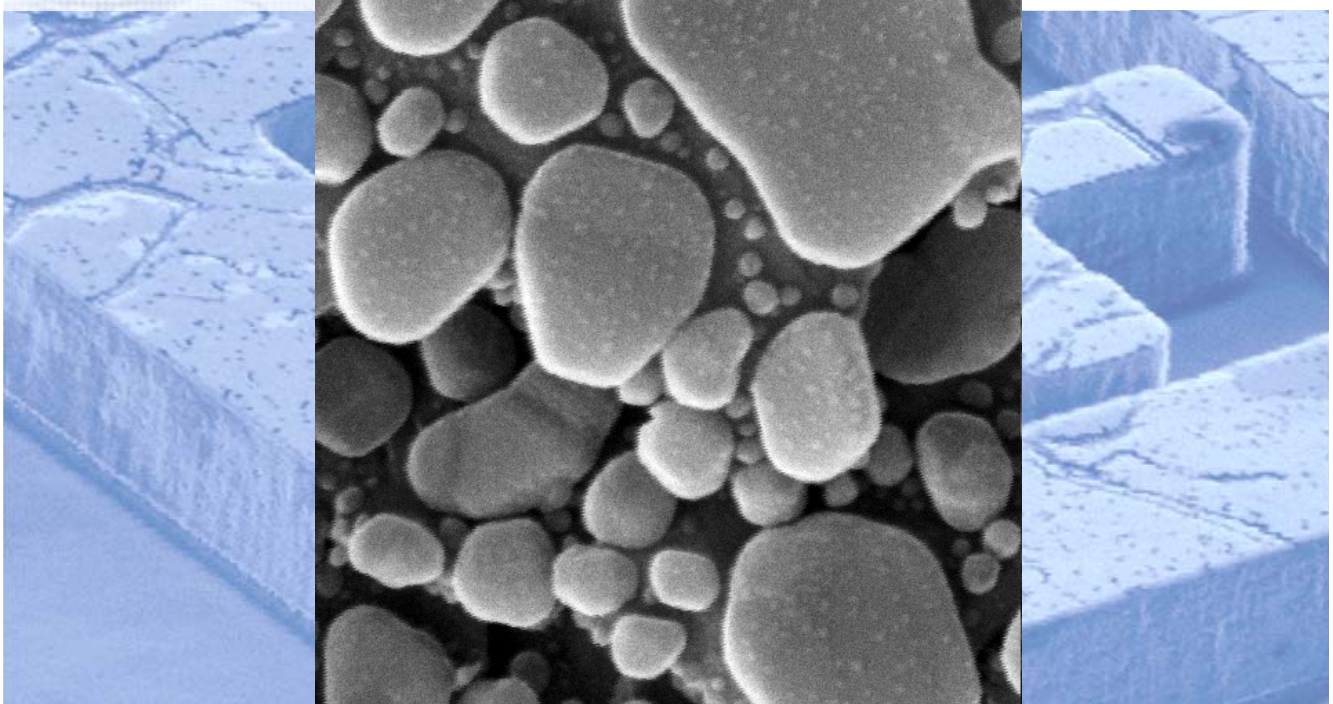


FWHM of dN/dE for a typical metal - ranges from 3 to 8 eV
 Result – No high energy electrons to blur e^- resolution

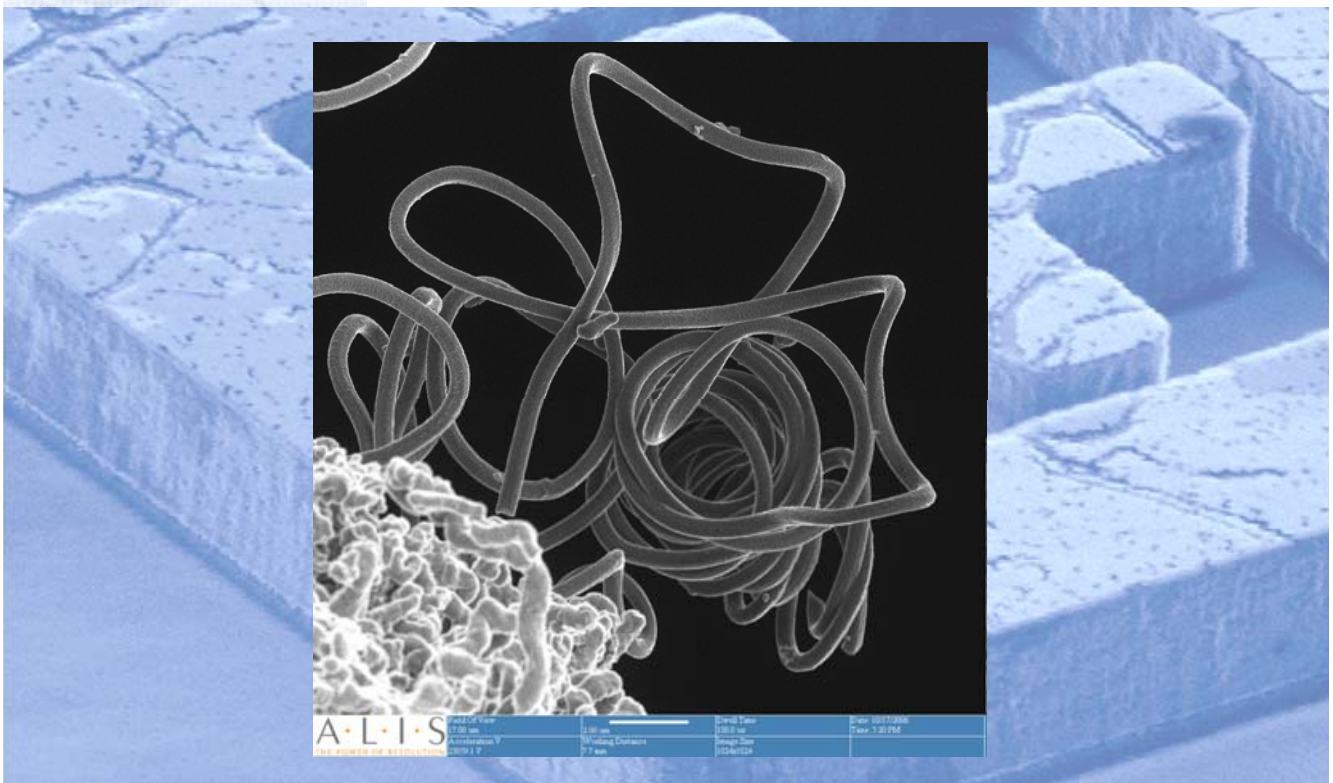


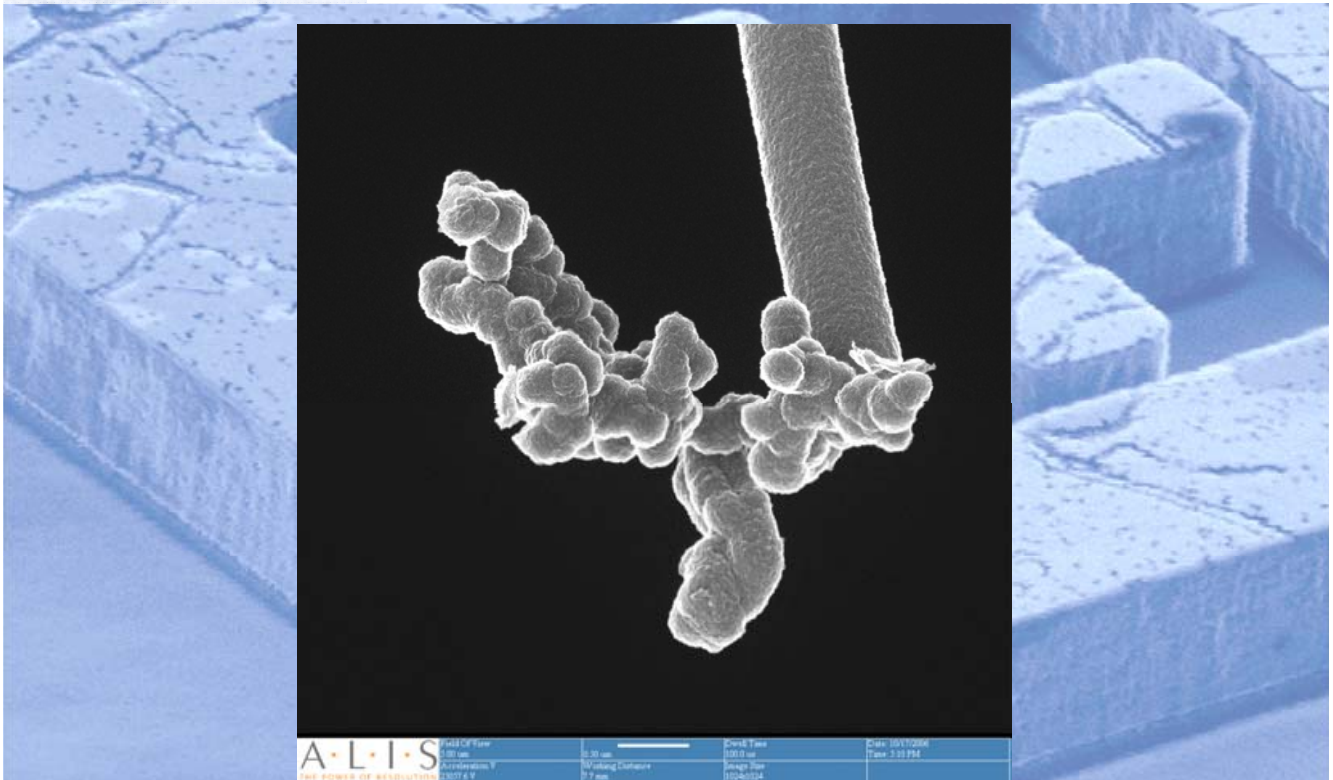
ALIS images offer rich
 surface information.





Gold condensate on carbon: 1 μm FOV.

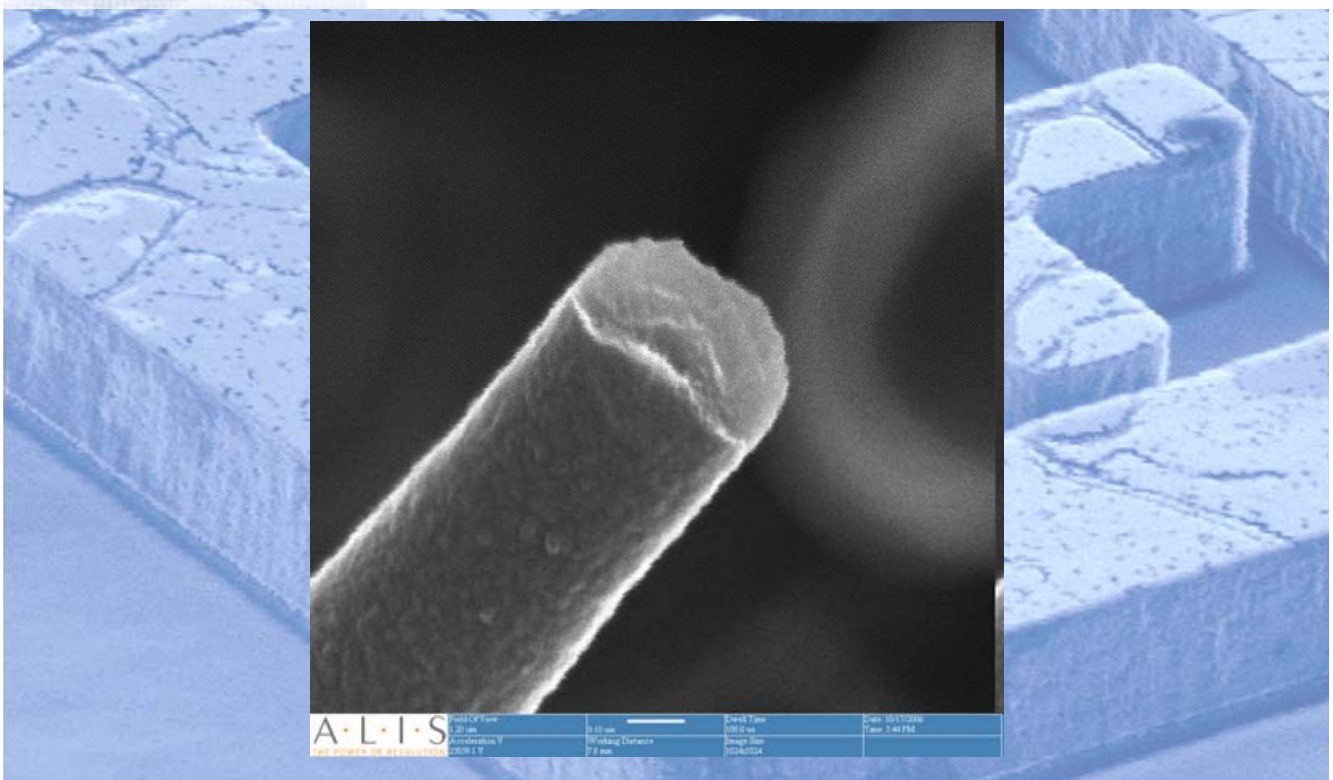




Confidential ALIS/Zeiss Material

Enabling the Nano-Age World®

Slide Number 27



Confidential ALIS/Zeiss Material

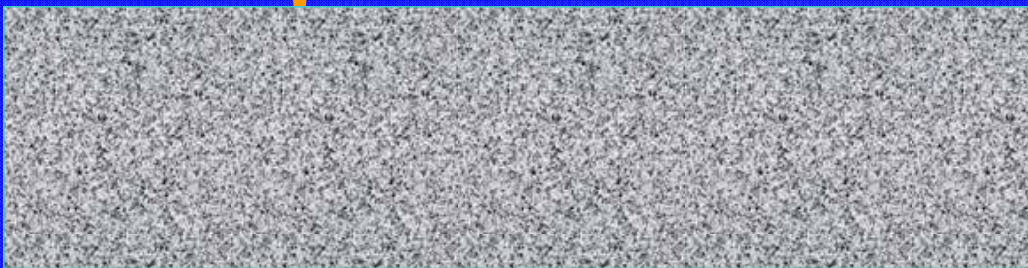
Enabling the Nano-Age World®

Slide Number 28

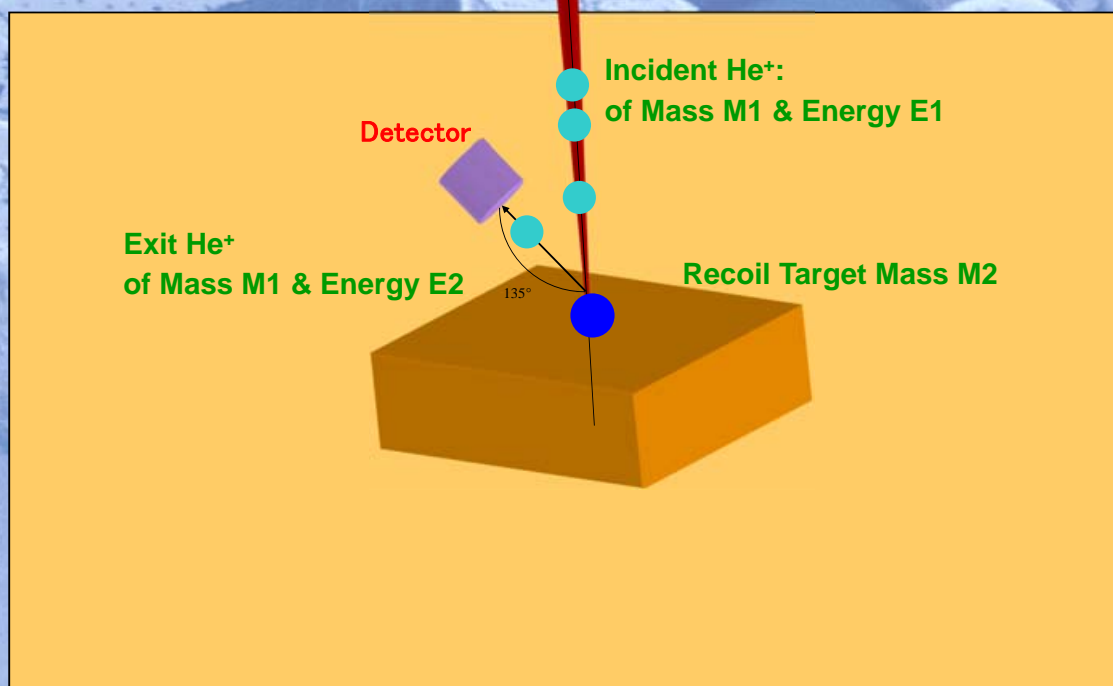


Back Scattered Helium:

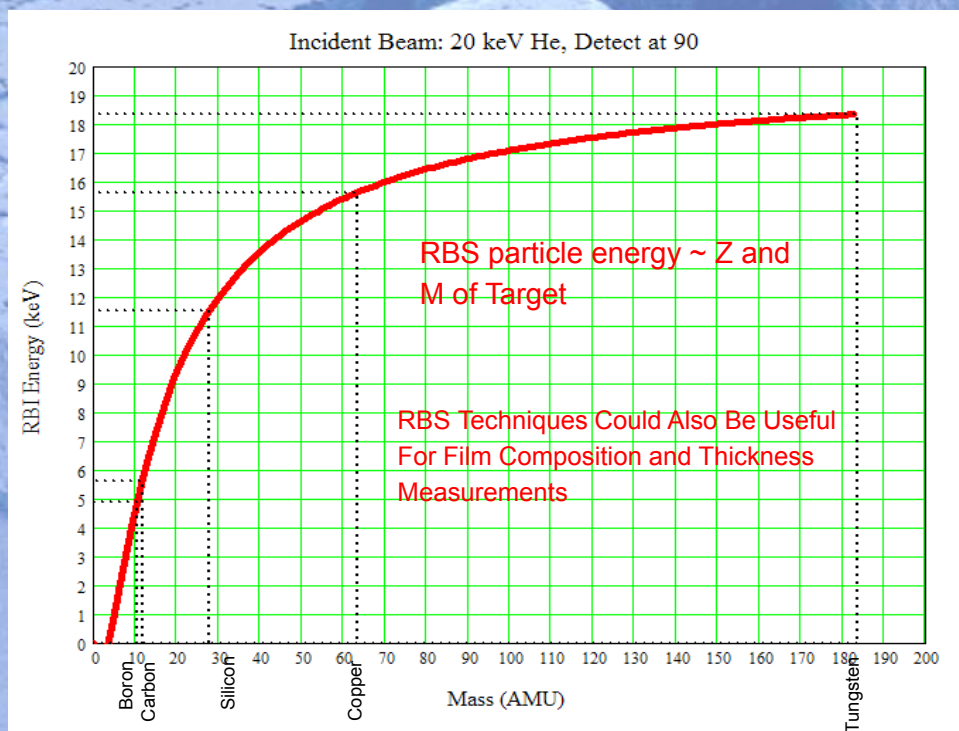
- Provides material information.
- Scatter yield varies with Z^2 of the target
- Scatter energy varies with mass of the target atoms (RBS)

**RBS Geometry:**

Recall Rutherford's
Experiment, Alphas (He^+)
on Gold Film



An RBS Image Gray Level is Material Dependent



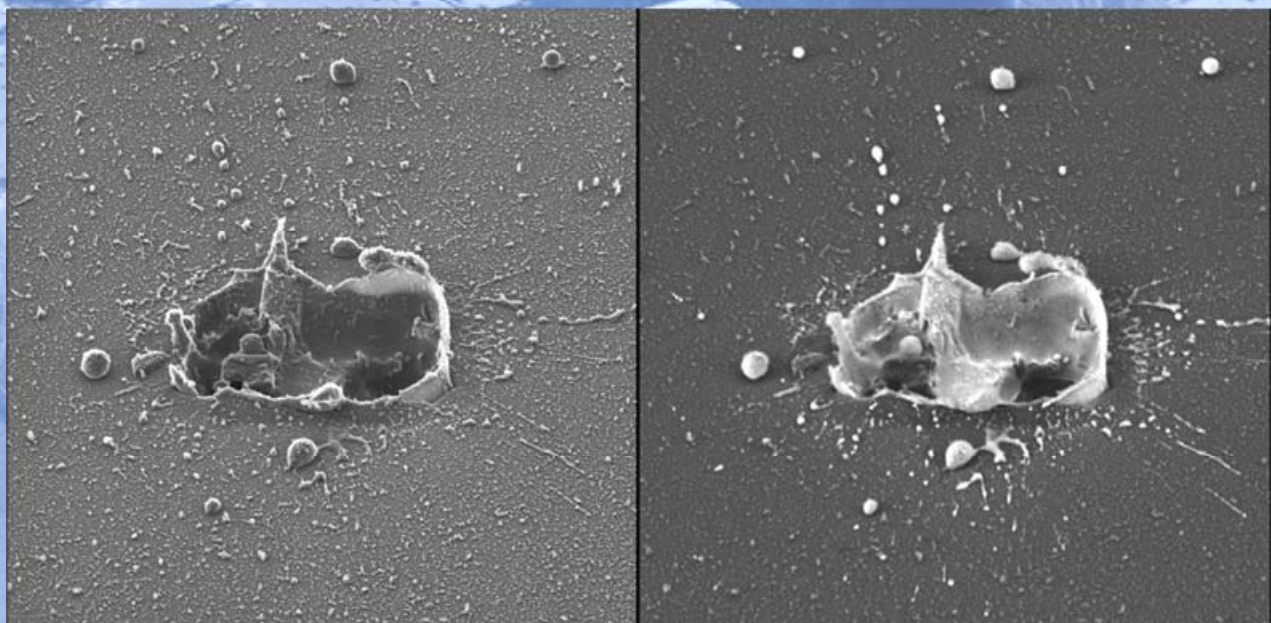
Confidential ALIS/Zeiss Material

Enabling the Nano-Age World®

Slide Number 31



ALIS SE vs. Backscattered Ion Images: Ablated Copper Over SiO₂



A·L·I·S

Beam: He(+), 1.1 pA, 18 keV
FOVh: 40 μ m
Tilt: 45 degDet: SE1
Sample: Lot23

A·L·I·S

Beam: He(+), 1.1 pA, 18 keV
FOVh: 40 μ m
Tilt: 45 degDet: RBS1
Sample: Lot23

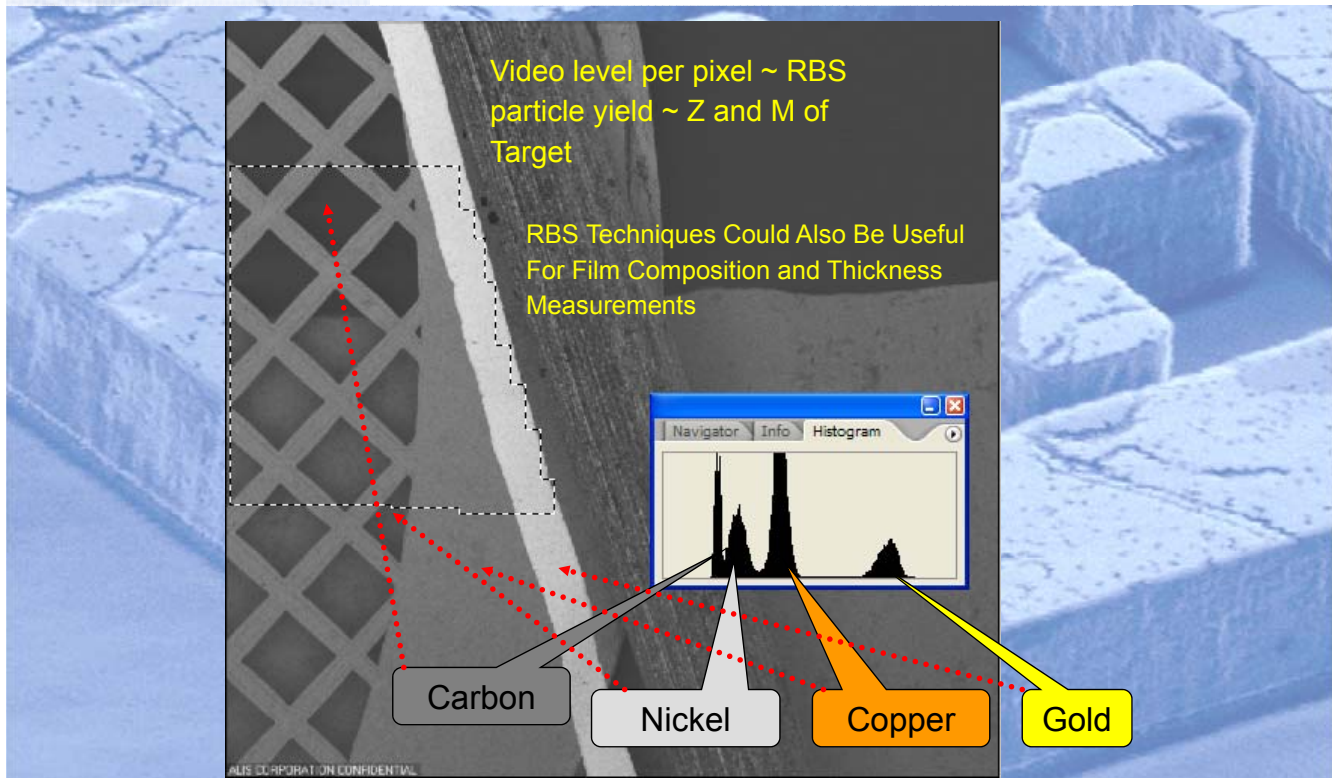
The SE image (left) shows great topographic information. The RBS Image (right) clearly differentiates the two materials.

Confidential ALIS/Zeiss Material

Enabling the Nano-Age World®

Slide Number 32



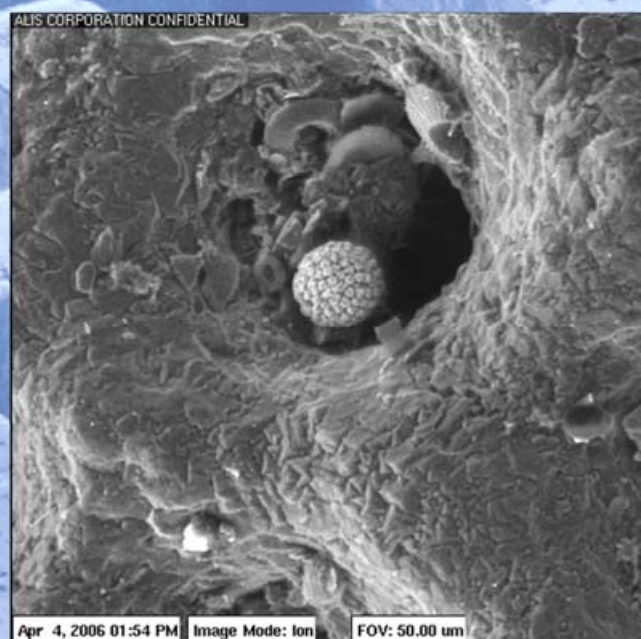


- Detected Count Rate Generally Increases with Target Atomic Number, Z_2
 - There are some shell closure (Screened Rutherford) effects
- Detected Count Rate Increases with Decreasing Energy, E
- Detected Count Rate Decreases with Increasing Detector Angle, θ
- Detected Particle Energy Increases with Target Mass, M_2
- Detected Count Rate ~ Video Level
- With Secondary Ion Count Rate Information, as well as Energy & Angle Information, Accurate Material Identification of Small Particles Seems Possible



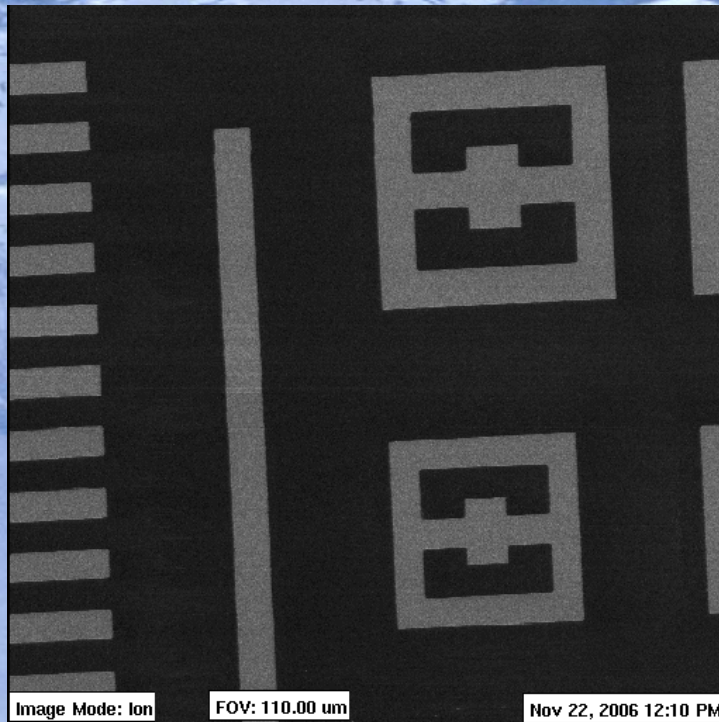
– Rutherford Backscattering Permits:

- Materials analysis from the video gray level
- RBS energy spectra & angular distributions may be able to uniquely determine small defects composition
- As well as thin film compositions



RBI images show no signs of charging on insulating materials.
Sample is Uncoated Benthic Foraminifera courtesy of WHOI.





He+

Sample:

Chrome on Quartz Mask

Field of view:~ 110 μm **Pixels:**

512 x 512

Comment:

No charging artifacts are seen between the dark material (quartz) and the light material (chrome). This image could not be obtained using a SEM. Scattered helium was used for generating this image.



- Because ions escape easily from ++ charged surface:
 - Less sample charging effects in the RBI images
 - Flood electron imaging a real option (There are no good ion flood guns and SEM energies must be tuned)

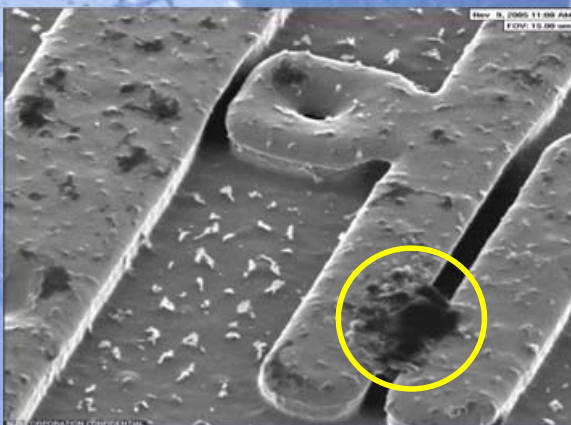


Comparison: ALIS SE vs. SEM

Confidential ALIS/Zeiss Material

Enabling the Nano-Age World®

Slide Number 39



The ALIS SE image (left) shows strong material contrast.



The traditional SEM image (right) appears “washed out”, and blurred due to SE2 contribution.

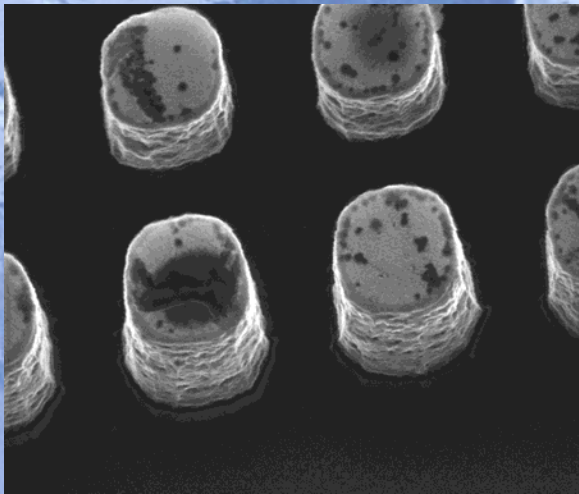
Confidential ALIS/Zeiss Material

Enabling the Nano-Age World®

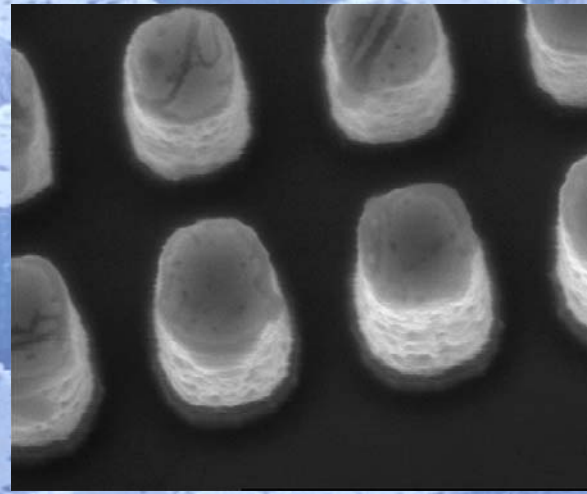
Slide Number 40



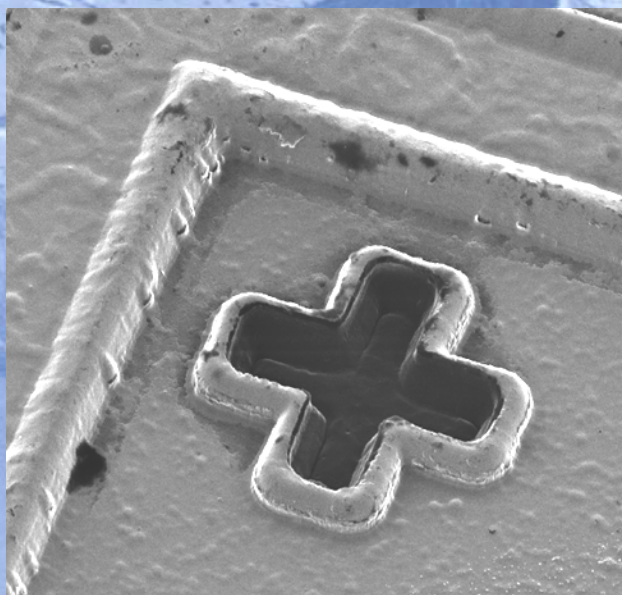
Al posts on Si: 3 μ m FOV



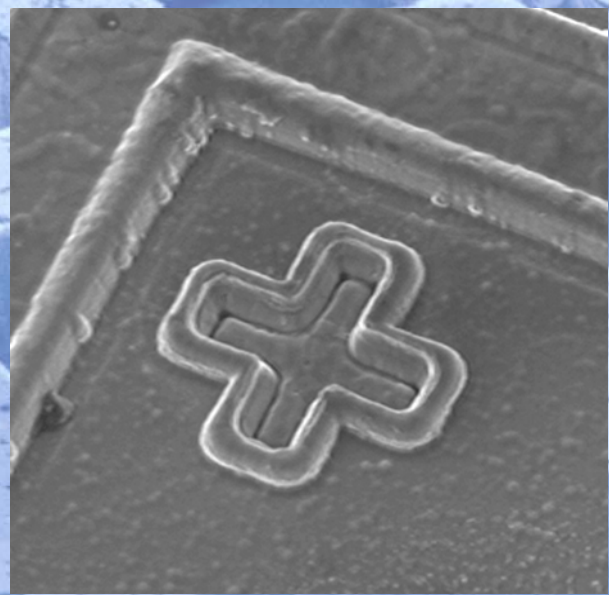
ALIS SE Image



SEM Image



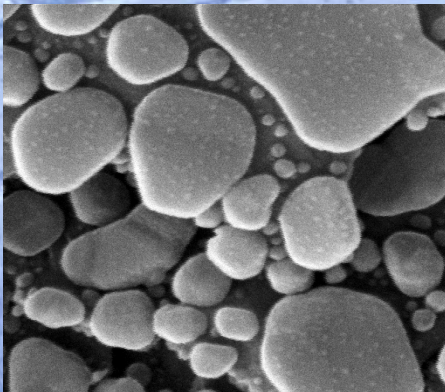
The ALIS SE image (left) shows a wider range of material contrasts.



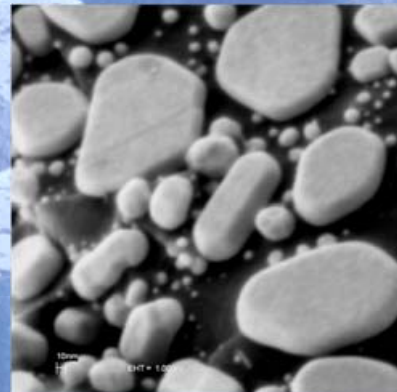
The image from the traditional SEM shows very limited grey scale range.



Comparison of He⁺ microscopy vs. SEM: Gold on Carbon

He⁺

Sample:
Gold on Carbon
Field of view:
1000 nm
Beam current:
He⁺ 1 pA
Dwell time:
100 μ s
Pixels:
512 x 512



SEM

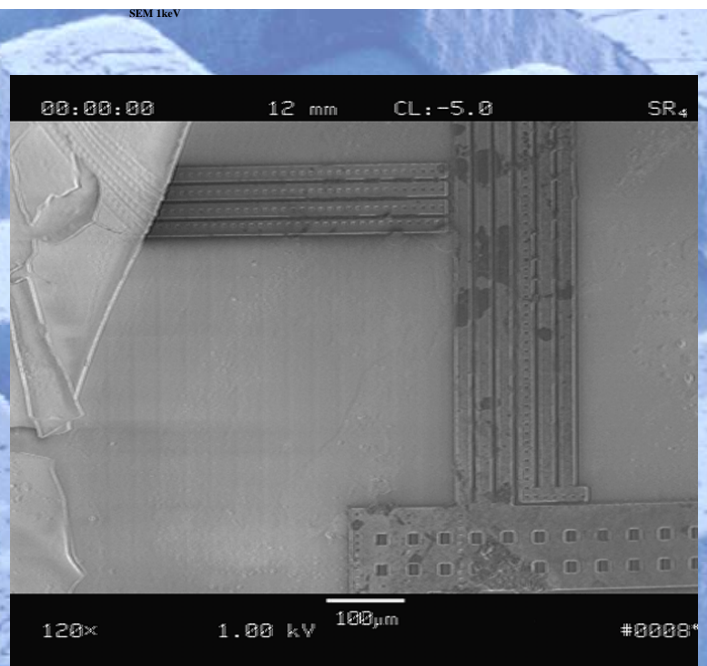
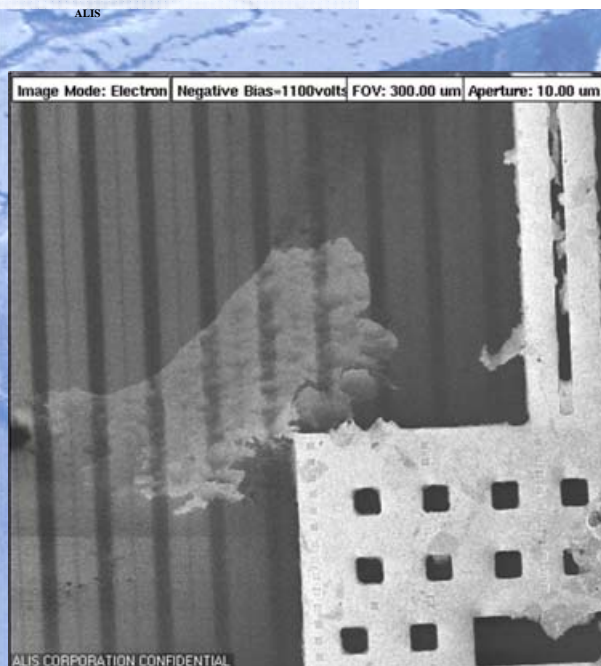
Sample:
Gold on Carbon
Field of view:
1000 nm
Beam:
Electrons, 1 kV

Resolution capability and surface sensitivity:

- High-energy He⁺ (30 kV) provide more surface information than low-energy electrons (1 - 3 kV), with only the uppermost surface area contributing to the SE signal.

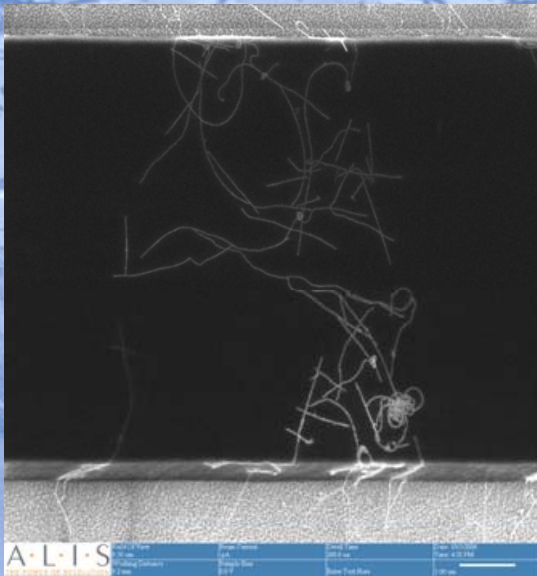


Enhanced surface/sub-surface imaging

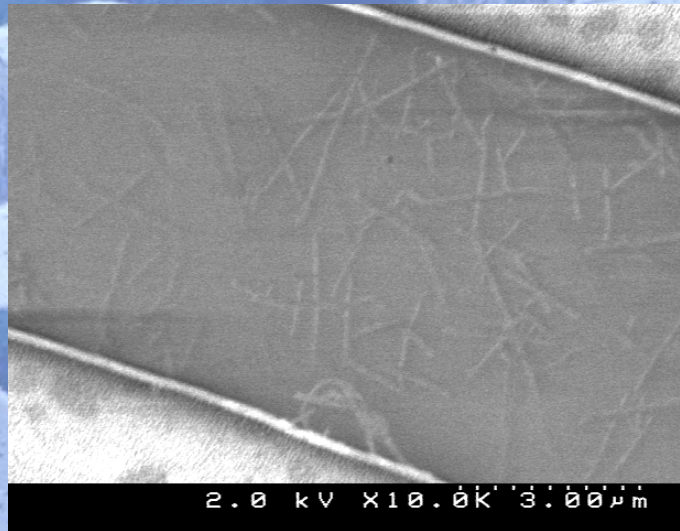


ALIS image reveals surface contamination not even visible in SEM





He+ image of nanotubes on silicon



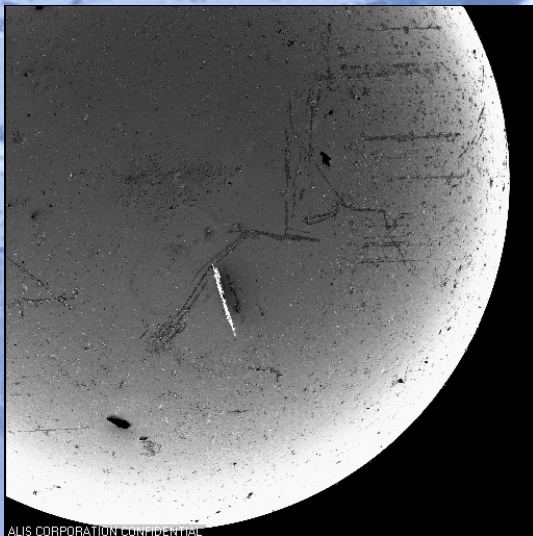
SEM image of nanotubes on silicon

High Contrast: He+ image (left) the carbon nanotubes clear.
Show high contrast.
SEM image (right) the carbon nanotubes are indistinct,
CNT's have little contrast relative to the background silicon.

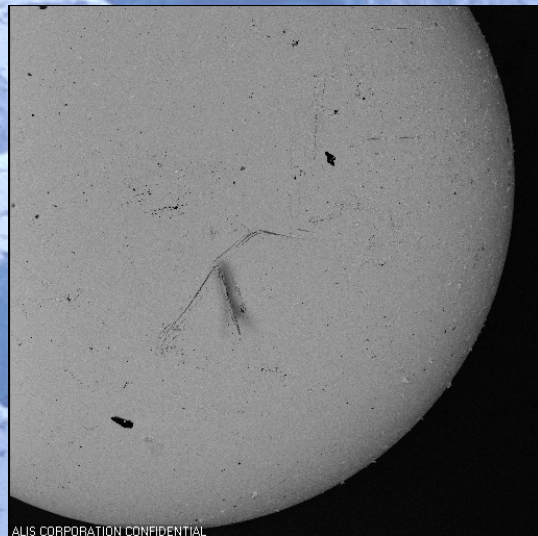


RBS Line Scans May Improve Line Width Measurement Information

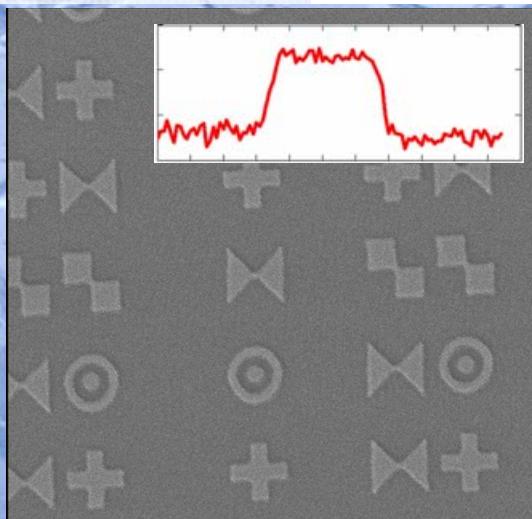




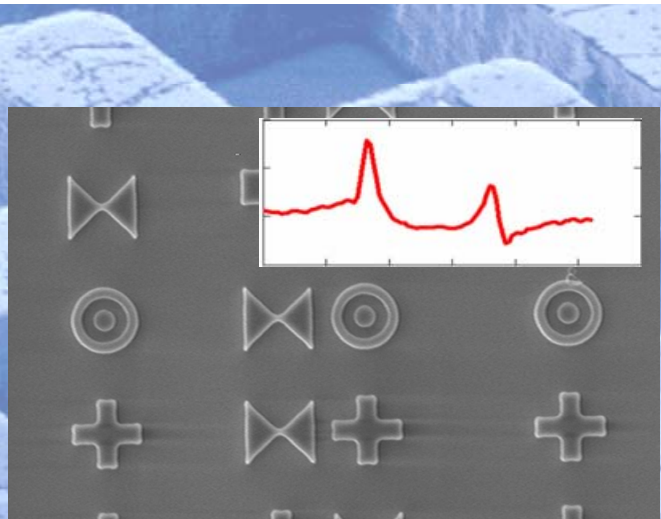
SE image shows topographic information that dominates over the material information.



With a proper selection of detector, the RBI Image shows little if any topographic information, so the material information dominates.



He+ Image



SEM Image

Reduced Edge Blooming:

The helium ion microscope can be configured to image with scattered helium. Under these circumstances, the topography is minimized and the image shows primarily material contrast. Thus edges are distinct transitions (left) without the edge blooming which can saturate the signal and obscure the edge location.



He Ion Channeling Another Contrast Mechanism

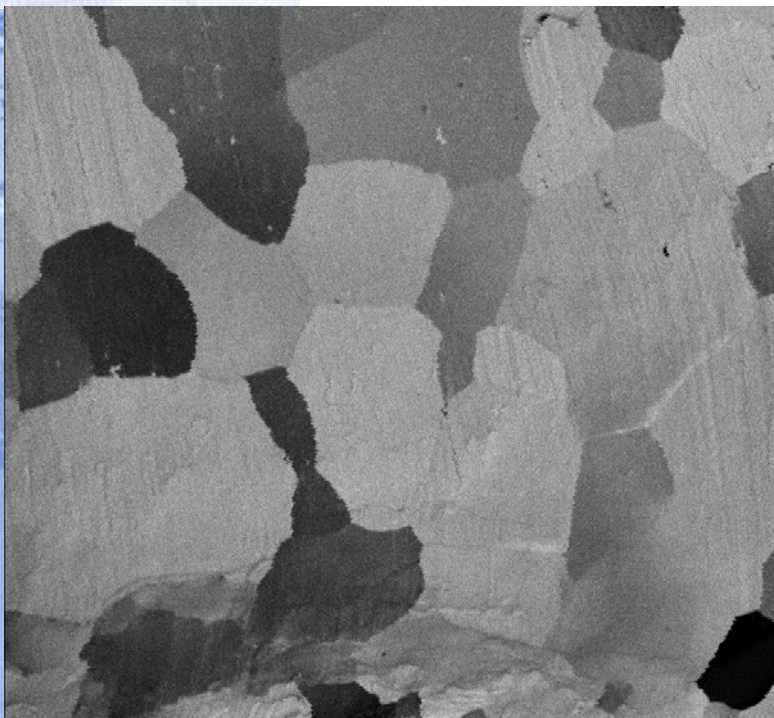
Confidential ALIS/Zeiss Material

Enabling the Nano-Age World®

Slide Number 49



He+ crystallographic Images: Channeling contrast



He+ image of the grain size of a weld

Sample:

Tungsten Weld

Field of view:

~ 100 µm

Pixels:

1024 x 1024

Comment:

In grains where the atoms are aligned parallel to the beam, the grain is dark.

In grains where the atoms are not aligned parallel to the beam, the grain is bright.

Potential: Further crystallographic information, like EBSD Kikuchi patterns may also be possible.

Confidential ALIS/Zeiss Material

Enabling the Nano-Age World®

Slide Number 50



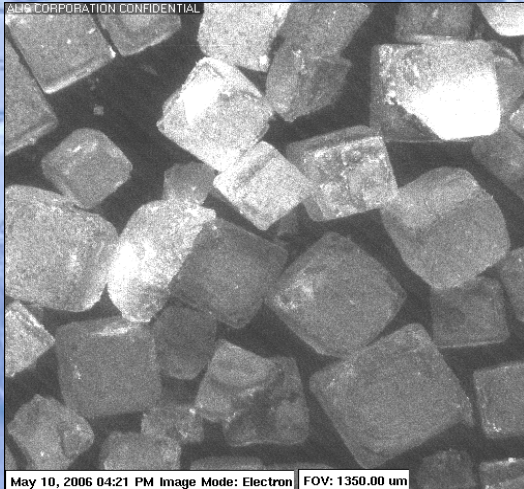
– Enhanced sensitivity to surface films because of:

- Large depth of He⁺ penetration
 - He⁺ induced SE's launch primarily from the surface
 - No high energy electron backscatter
- Extremely localized SE launch location
 - Vs large primary electron interaction volume in high resolution SEMs

**Photon Production:**

- Provides material information
(*some materials only*)
- Includes sample de-excitation
- Includes Helium de-excitation





May 10, 2006 04:21 PM Image Mode: Electron FOV: 1350.00 um

He+ photon image of table salt

Sample:

NaCl (table salt)

Field of view:

~ 1300 μm

Detector:

photons only

Comment:

The signal in this case is generated from photons generated from the helium beam. The photons are partly from sample de-excitation, and partly from helium de-excitation.



■ Helium Ion Microscope Advantages

- Ultimate Spot size: $d_{50} = 1/4 \text{ nm}$
 - High Brightness: $> 3.4 \times 10^9 \text{ A}/(\text{cm}^2 \text{ sr})$
 - Small Virtual Source Size (Sub-Angstrom)
 - Reduced Diffraction Effects compared to SEM
 - Low energy spread ($\sim 1/2 \text{ eV}$)
- Long Source Lifetime and Stability
- Small sample interaction volume
- Image Information:
 - Topographic information
 - Material information
 - Voltage Contrast Information
 - Crystallographic information
 - Minimized charging artifacts
 - Good S/N with low beam currents.
 - Long depth of field
 - Images from electrons, ions and photons available
- Analytical Information:
 - From RBS ions' Yield, Energy, and Angle
- Many Applications Completely Unexplored



Overview

• Application	General Microscopy
• Ultra-High Resolution (Goal)	0.25nm
• Ultra-High Contrast	Material/Chemical/Crystallographic
• Multiple Imaging Modes	SE (Secondary Electron) RBI (Rutherford Backscattered Ions)



Resolution:	Goal	0.25 nm @ 45 kV @ 4 mm WD
	Currently Committed	1.0 nm @ 40 kV @ 4 mm WD
		3.0 nm @ 10 kV @ 4 mm WD
Magnification		100X – 1,000,000X
Field of View		1 mm – 100 nm
Sample Working Distance		4 mm – 15 mm
Source Type		He ion field emitter
Probe Size		≤1nm @ 1 pA
Accelerating Voltage	Goal	500 V – 45 kV
	Committed	10 kV – 45 kV
Probe Current		1 fA – 25 pA
Charge Neutralization		Yes



Standard Detector	Everhart-Thornley Detector
Multiple Detector Capable	Yes
Sample Size Range	Up to 50mm x 50mm
5-Axis Motorized Sample Stage	50mm x 50mm X-Y, 12mm Z 360° θ , +45° tilt, - 5° tilt
SIM Image Acquisition	Up to 8196 x 8196 pixels
SIM Image Displayed	Up To 2048 x 2048 pixels (1024 x 1024 viewable)
System Displays	Dual 1680 x 1050 TFT Displays
System CPUs	1 Standard, 2 nd Optional
System Control	Windows® XP Operating System Mouse, Keyboard, Control Panel Optional Gamepad Controller



1	High resolution
2	Surface Sensitivity
3	Low Z (carbon) imaging ability
4	Large Depth of Field
5	Room for Future Hardware – New detectors etc.
6	Productivity – Stage can move fast
7	RBI Mode determines materials from video level
8	Particle & Thin Film Analysis in RBI Mode
9	Images n, p, n+ & p+ in Si trenches & cross sections
10	In RBI (ion) mode, less charging & e ⁻ flood OK
11	Crystal grain orientation produces contrast variation
12	In RBI mode better CD measurement tools may be possible w/ He+
Others	No Ga Staining, No Electrical Invasiveness & No Edge Blooming as in SEM



The END

